

PATENT

Date of Notice
of Allowance : December 19, 2008

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Marti Carrillo

Applicant	: Kim, Nam Hun	Confirmation No. 5813
Application No.	: 10/593,857	
Filed	: September 22, 2006	
Title	: PLASMA CHAMBER HAVING PLASMA SOURCE COIL AND METHOD FOR ETCHING THE WAFER USING THE SAME	
Grp./Div.	: 1792	
Examiner	: Duy Vu Nguyen Deo	
Docket No.	: 58409/N305	

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Post Office Box 7068
Pasadena, CA 91109-7068
March 17, 2009

Commissioner:

Reasons for allowance are only warranted in instances in which "the record of the prosecution as a whole does not make clear his or her reasons for allowing a claim or claims." (37 CFR § 1.104(e))

Applicant believes the Examiner's stated reasons for allowance are unnecessary. The applicant does not necessarily agree with each statement in the reasons for allowance. While applicant agrees that the claims are allowable, applicant does not acquiesce with each statement in the reasons for allowance, that patentability requires each stated feature exactly as expressed by the Examiner, nor that each stated feature is required for patentability.

**Appln No. 10/593,857
Stmt date March 17, 2009**

Respectfully submitted,
CHRISTIE, PARKER & HALE, LLP

By D. Bruce Prout

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DBP/mac

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